



+ IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicants: Chen et al. Group Art Unit: 1756

Serial No.: 09/941,537 Examiner: J. S. Ruggles

Filed: 08/29/2001 In Response to Office Action  
Dated: 04/06/2004

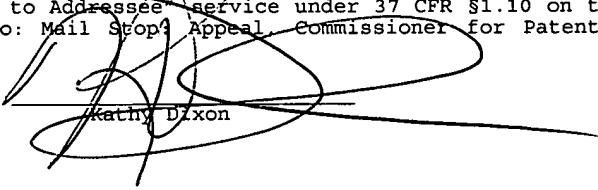
For: METHOD FOR REDUCING LIGHT REFLECTANCE IN A PHOTOLITHOGRAPHIC  
DUAL DAMASCENE TRENCH PATTERNING PROCESS

Attorney Docket No.: 67,200-477

**EXPRESS MAIL CERTIFICATE**

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Kathy Dixon

**SUPPLEMENTAL AMENDMENT**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, Va 22313-1450

Dear Sir:

In response to Advisory Actions mailed 04/06/2004  
Applicants respectfully request entry of the following amendments  
to place the Application to remove issues from Appeal and comply  
with Examiners requirements and/or suggestions. Please consider  
the following remarks.